

Article

# Tunable Iron–Cobalt Thin Films Grown by Electrodeposition

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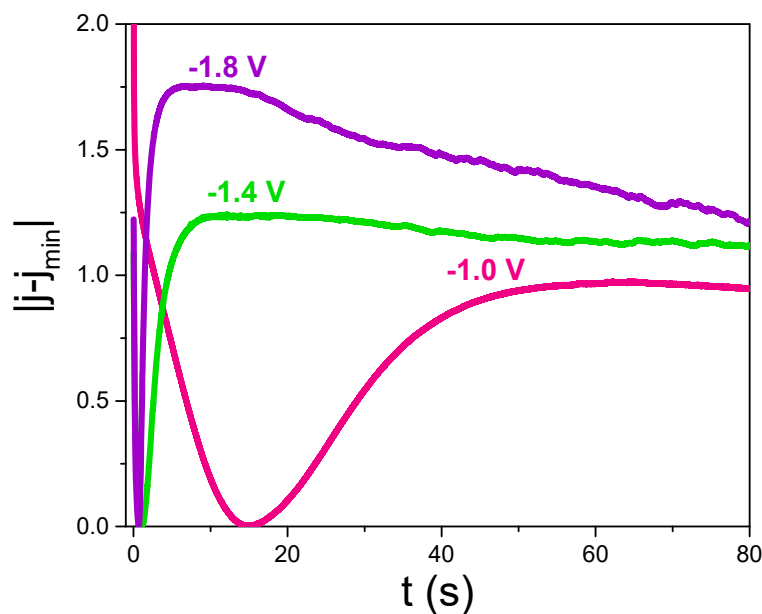
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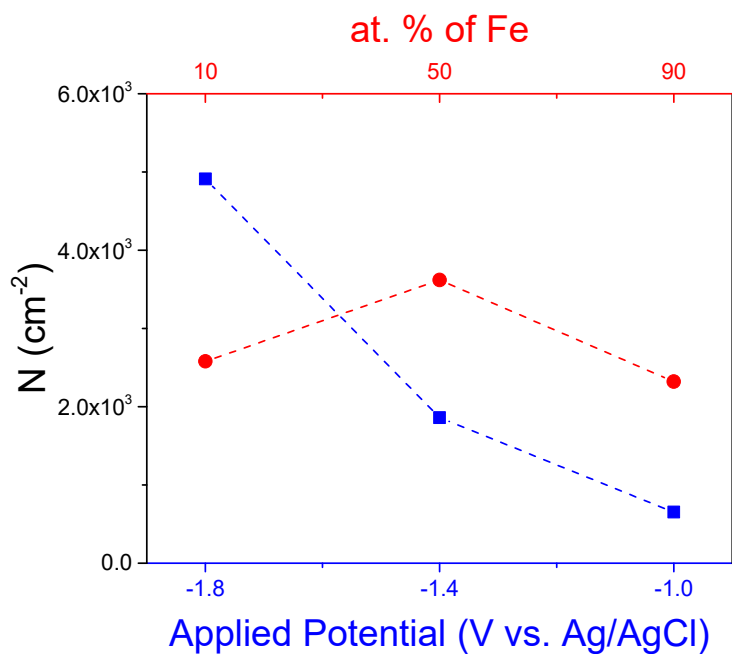
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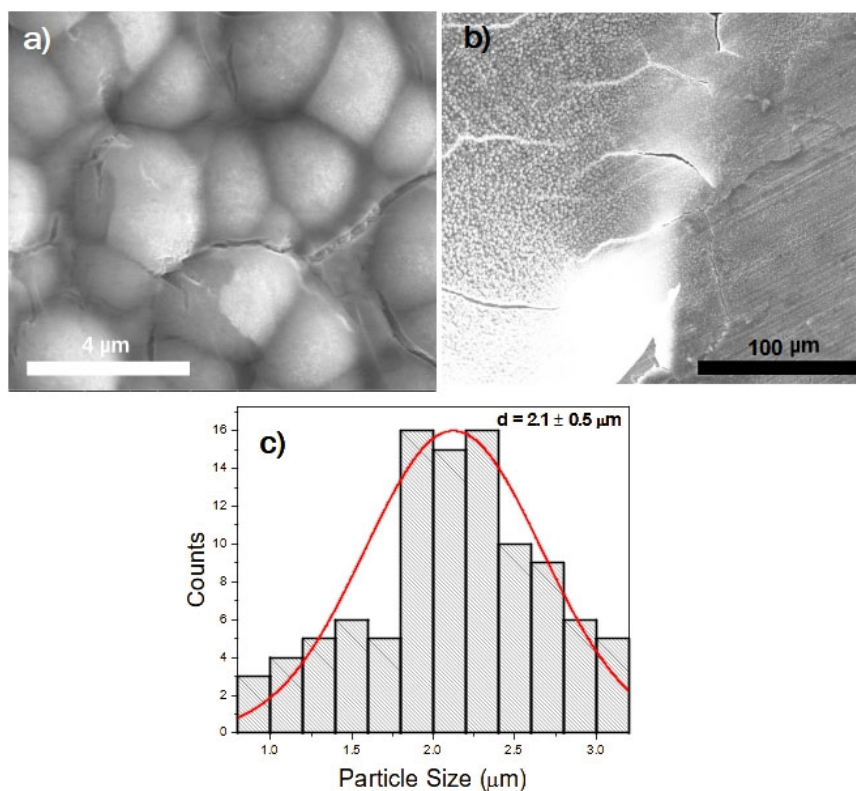
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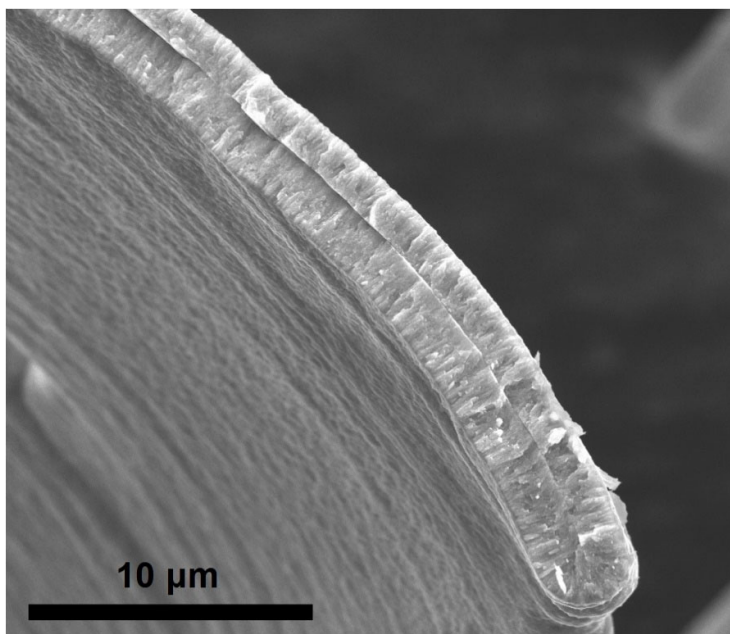
**Figure S1.** Overall  $j-j_{\min}$  as a function of time to illustrate that the  $t_{\max}$  increases with  $V_{\text{dep}}$



**Figure S2.** Number of nuclei vs. applied potential (blue squares) and vs. applied potential (red circles) for the electrodeposition of FeCo on Cu substrate.



**Figure S3.** (a) and (b) Top view of the thin film electrodeposited on Cu substrate using the electrolyte 1 at electrodeposition potentials of - 1.4 V, and its corresponding (c) particle size distribution histogram.



**Figure S4.** Cross-section SEM image (secondary electrons) of the thin film electrodeposited in Cu substrate using the electrolyte.

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